



Correction: Atomic layer deposition of a MoS₂ film

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Correction for 'Atomic layer deposition of a MoS₂ film' by Lee Kheng Tan *et al.*, *Nanoscale*, 2014, **6**, 10584–10588.

(1) There is an error to the existing author list. The correct list should be:

Lee Kheng Tan,^{‡ab} Bo Liu,^{‡c} Jing Hua Teng,^b Shifeng Guo,^b Hong Yee Low,^d Hui Ru Tan,^b Christy Yuen Tung Chong,^b Ren Bin Yang,^b and Kian Ping Loh^{*a}

(2) There is an error in the Acknowledgements. It should read:

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The Royal Society of Chemistry apologises for these errors and any consequent inconvenience to authors and readers.

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